

Three-step lithography to the fabrication of vertically coupled micro-ring resonators in amorphous silicon-on-insulator-corrigendum

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The authors would like to apologize for three errors in the paper on Chinese Optics Letters vol. 13, no. 8, page 082201.

On page 082201–1, the second author is “Duk-Yong Choi” (not Nan Yan), and the corresponding author is “duk.choi@anu.edu.au” (not Jun Cheng). On page 082201–2, a reference should be added for the Fig. 2 (X. Gai, D.-Y. Choi, and B. Luther-Davies, *Opt. Exp.* **22**, 9948 (2014)). On page 082201–4, line 29, should be “6 and 8 dB/cm” (not 2.6 and 3.2 dB/cm).

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References

1. J. Cheng and N. Yan, *Chin. Opt. Lett.* **13**, 082201 (2015).